Diagnosis

- **Introduction**
- **Logic Diagnosis**
- **Scan Chain Diagnosis**
- **Failure Analysis *(not in exam)**
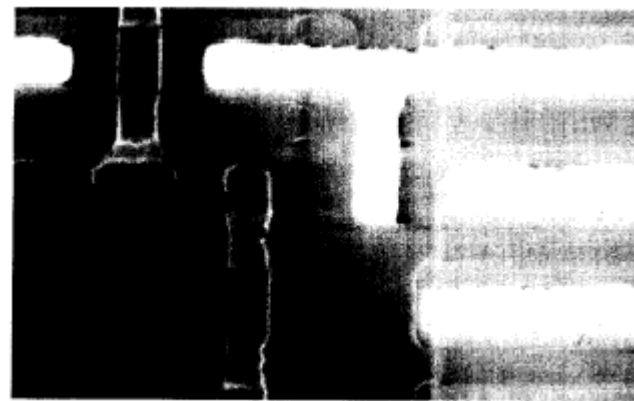- **Conclusions**

Physical Failure Analysis, PFA

- **What is PFA**
  - ♦ **Open chip package, locate and examine failure mode of defect**
  - ♦ **Aka.**
    - ∗ *Failure Analysis (FA)*

- **Why PFA**
  - ♦ **Verify diagnosis results**
  - ♦ **Improve fab/test/design**
    - ∗ **Improve yield**
  - ♦ **Improve design or test techniques**

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Failure Analysis

- **Examine failure mode of defects**
  - **Failure mechanism can be inferred**
- **Usually requires lots of experience and equipments**

- **Example FA pictures [Soden 89]**
  - **Scanning Electron Microscope picture (Voltage Contrast)**
  - **Failure mechanism: photoresist failed to adhere**
  - **Failure mode: open circuit**
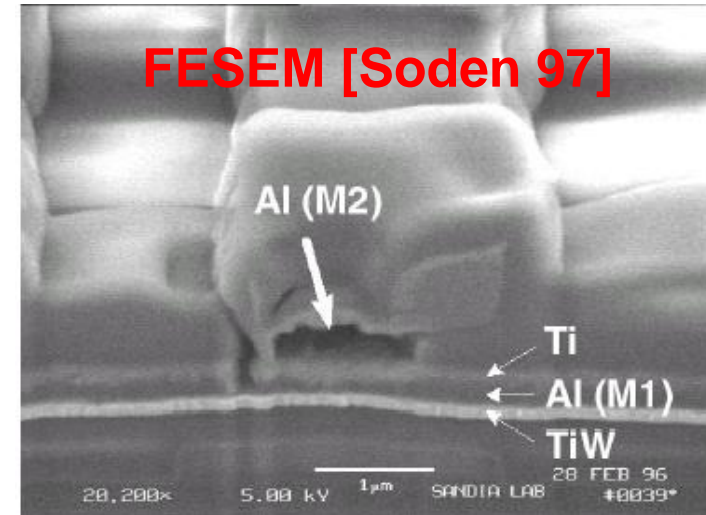

good

defective

FA Techniques

- **Imaging without power**

- **Imaging with power**

- **Physical process**
  - ♦ **Etching, cross sectioning**

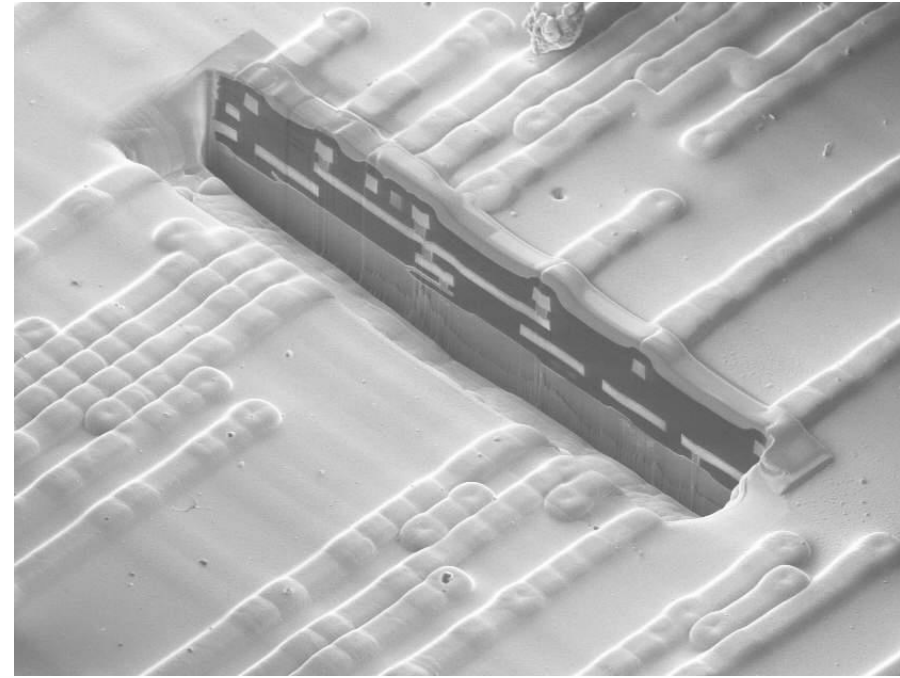- **See more details [Soden D&T 97]**

Imaging Techniques (no power)

- **Optical microscope (Resolution limit :0.2 to 0.3 μm)**
  - **One useful technique: Scanning Optical Microscope (SOM)**
    - **focus infrared laser spot scanning over sample**
      - **Silicon transparent to infrared**
      - **Resolution limit: 1μm**
- **Scanning Electron Microscope (SEM)**
  - **Field emission Scanning Electron Microscope (FESEM)**
    - **Resolution limit: 2 to 5 nm**
  - **Transmission Electron Microscope (TEM)**
    - **Resolution: sub nm**
- **Scanning probe microscope (SPM)**
  - **Sharp probe tip scans sample surface**
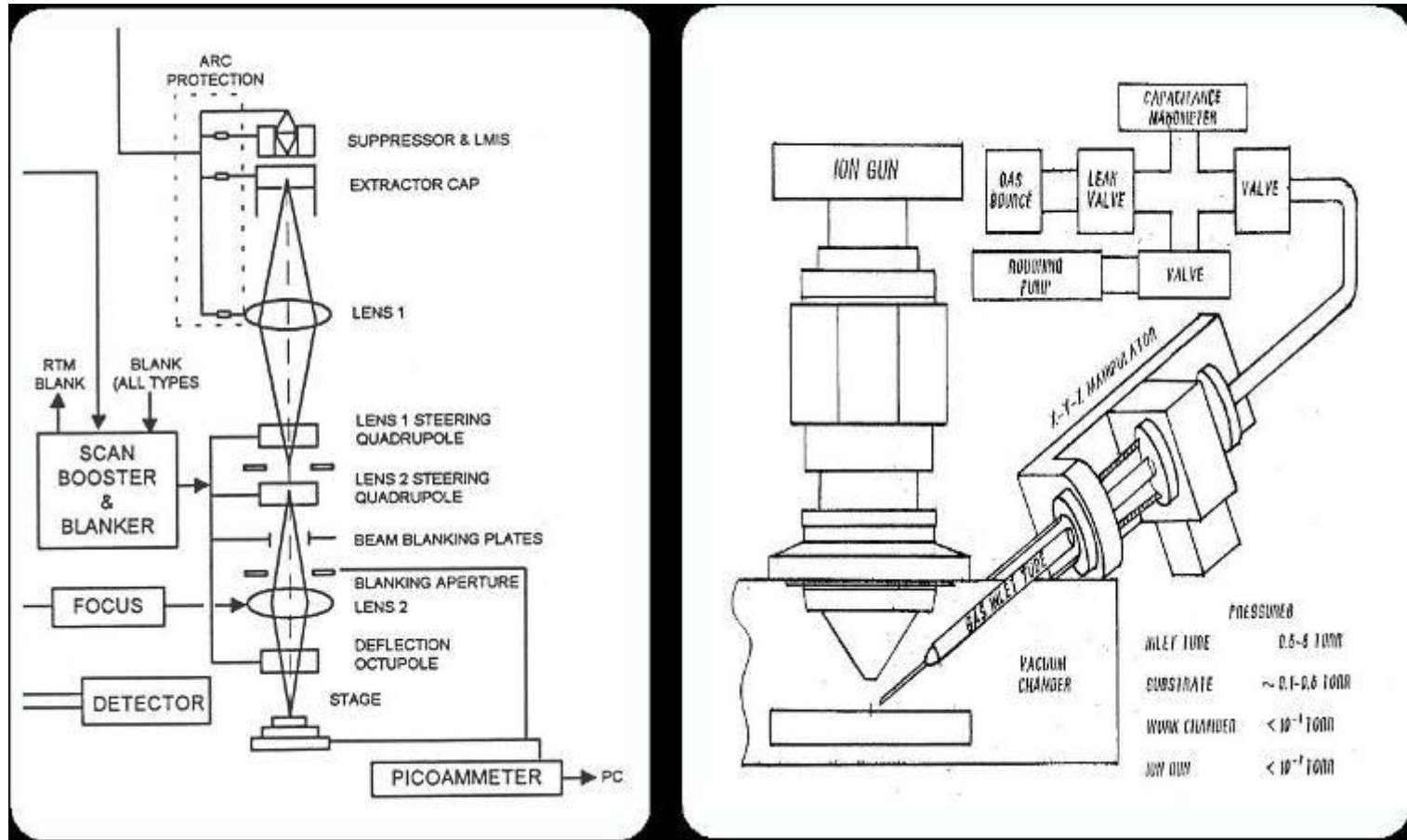- **Focus Ion Beam (FIB)**

FESEM [Soden 97]

Al (M2)

Ti
Al (M1)
TiW

20,200x   5.00 kV   1µm   SANDIA LAB   28 FEB 96   #0039

Focus Ion Beam (FIB)

- **Focused beam of Ga$^+$ ion**

- **Multiple usages**

    - **Image**

    - **Circuit editing (down to 45 nm),**

    - **FA cross-sectioning (wider than 200um) with e-beam imaging and ion channeling contrast**

    - **Ion Channeling Contrast for grain imaging of crystalline materials**

    - **Passive Voltage Contrast for FA**

    - **Micro-machining for MEMS**

    - **TEM sample preparation, both cross-sectional and plan-view (min. size 18 nm)**

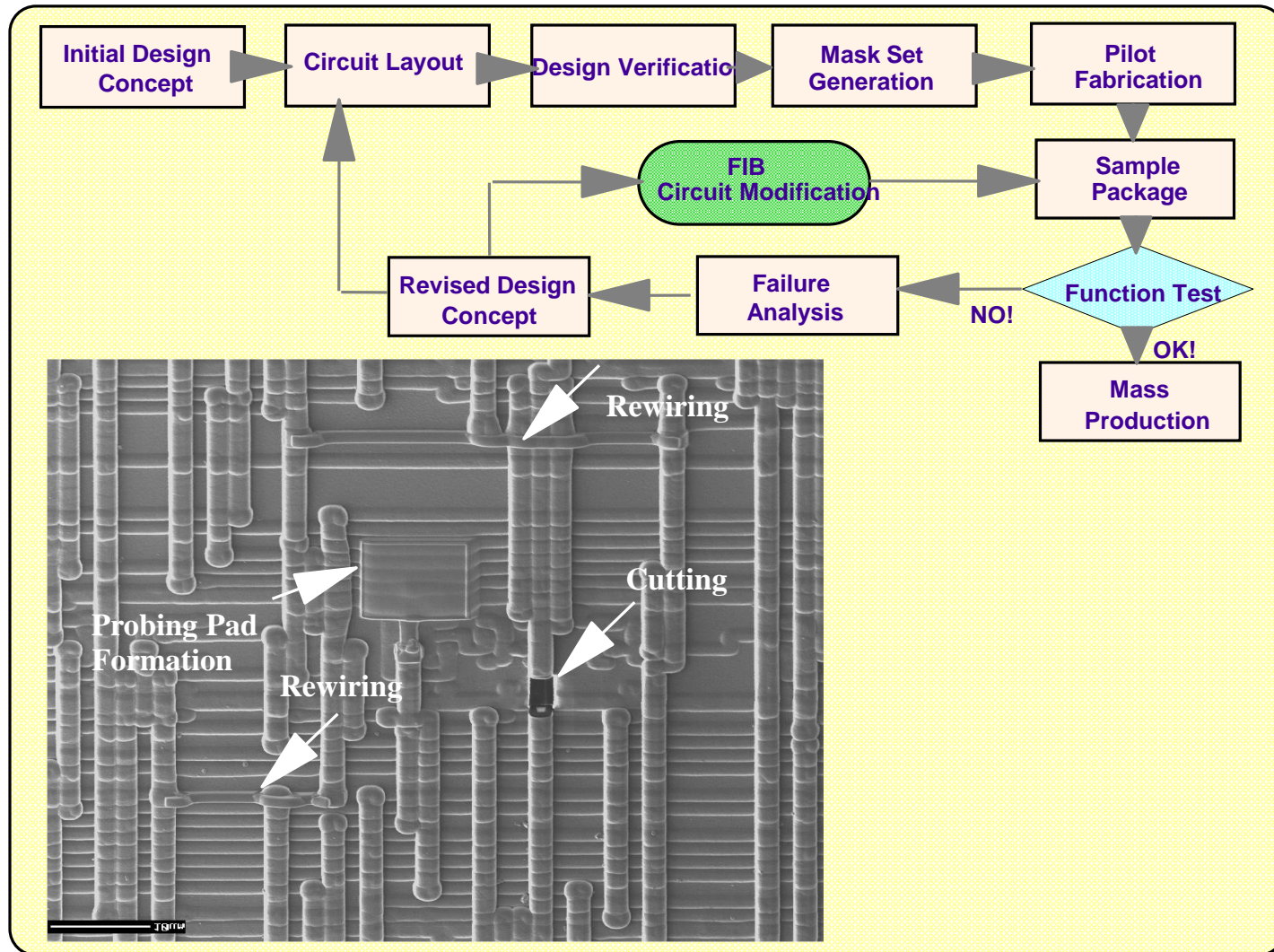   - **Ion implantation (Ga$^+$)**

[image courtesy of SK Lu from FJU]

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FIB system

FIB photo

- **Source : MA TEK**

FIB Circuit Editing

Initial Design Concept → **Circuit Layout** → **Design Verification** → **Mask Set Generation** → **Pilot Fabrication**

FIB Circuit Modification → **Sample Package**

Revised Design Concept ← **Failure Analysis** ← NO! ← **Function Test**

Function Test → OK! → **Mass Production**

Rewiring

Cutting

Probing Pad Formation

Rewiring

Imaging Techniques (powered)

- **Light emission (aka photo emission microscope)**
  - ♦ **Apply test patterns, capture light by camera**
  - ♦ **Very commonly used**
    - + **Feature size independent**
    - + **Infrared light enable analysis form die backside**
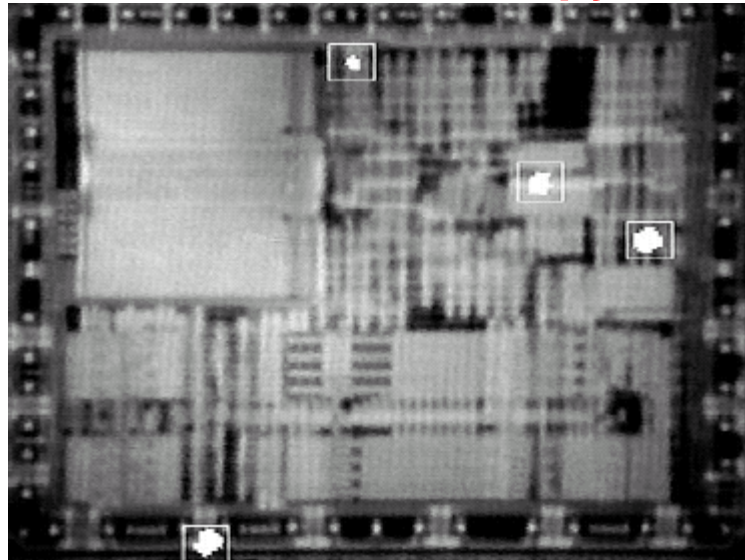
Light emission microscopy [Soden 97]

Figure 2. Low-magnification light emission microscopy image of a 32-bit microprocessor with four gate oxide shorts (bright areas in the four boxes).

Imaging Techniques (powered)

- **Voltage Contrast (VC) and Electron Beam (E beam)**
  - **Probe change of signals as well as voltage measurement**
    - **+ Nondestructive**
    - **– Cannot probe Flip chip package**
    - **– More nose for small geometry and high frequency**
    - **– Difficult to probe lower layer of metals**
- **Resistive Contrast Imaging (RCI)**
  - **SEM that generates relative resistance image between two nodes**
  - **Useful for open defects**

RCI [Soden 97]

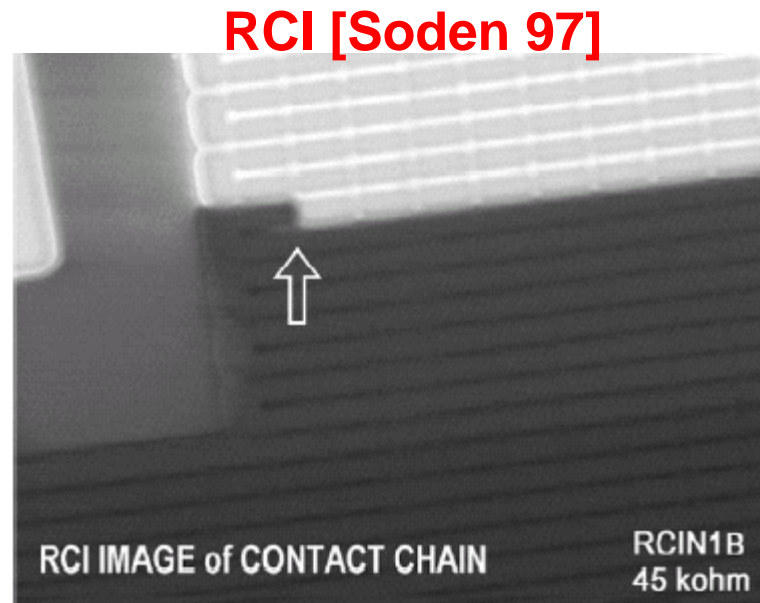RCI IMAGE of CONTACT CHAIN   RCIN1B 45 kohm

Figure 11. RCI image of contact chain with contrast discontinuity at high-resistance contact (arrow).

Imaging Techniques (powered)

- **Charge and Light-Induced Voltage Alteration (CIVA/ LIVA)**
  - ♦ **Useful for open defects**
- **Scanning Probe Microscope**
- **FIB**
- **Thermal imaging**
  - ♦ **Detects "hot spots" caused by defects**
  - ♦ **Commonly used techniques:**
    - ∗ **Liquid crystal**
    - ∗ **Infrared thermography**

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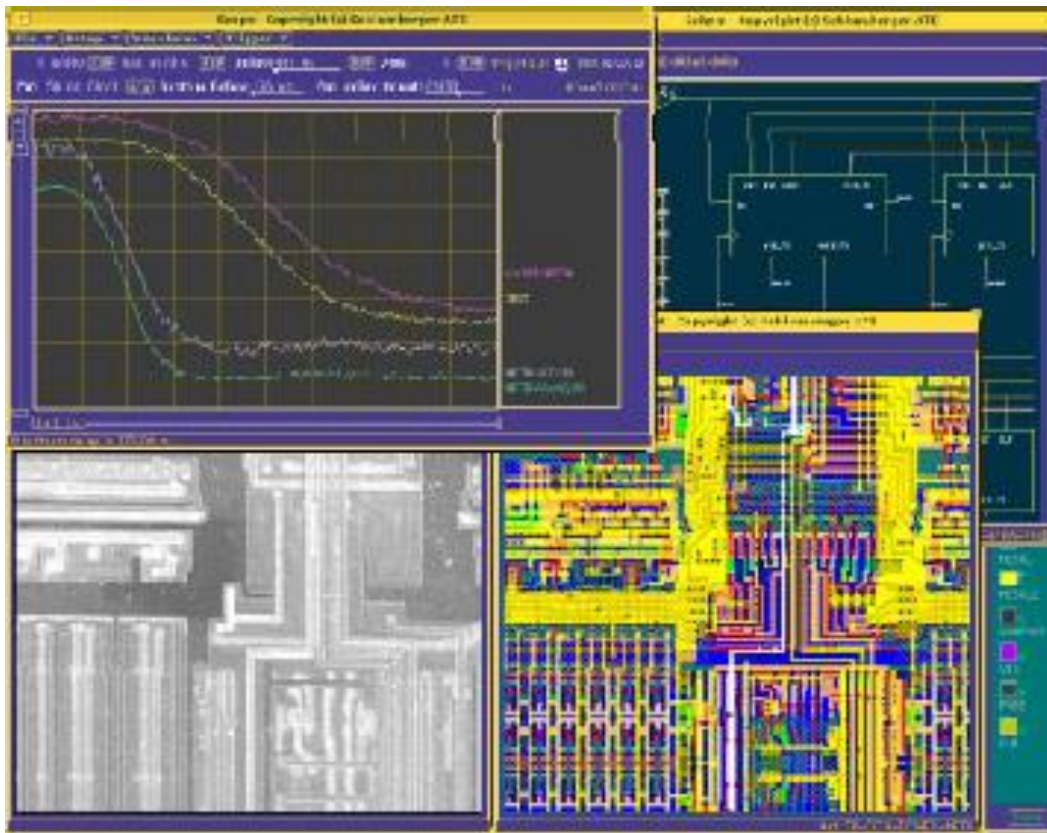# Integrated E-Beam Probe System

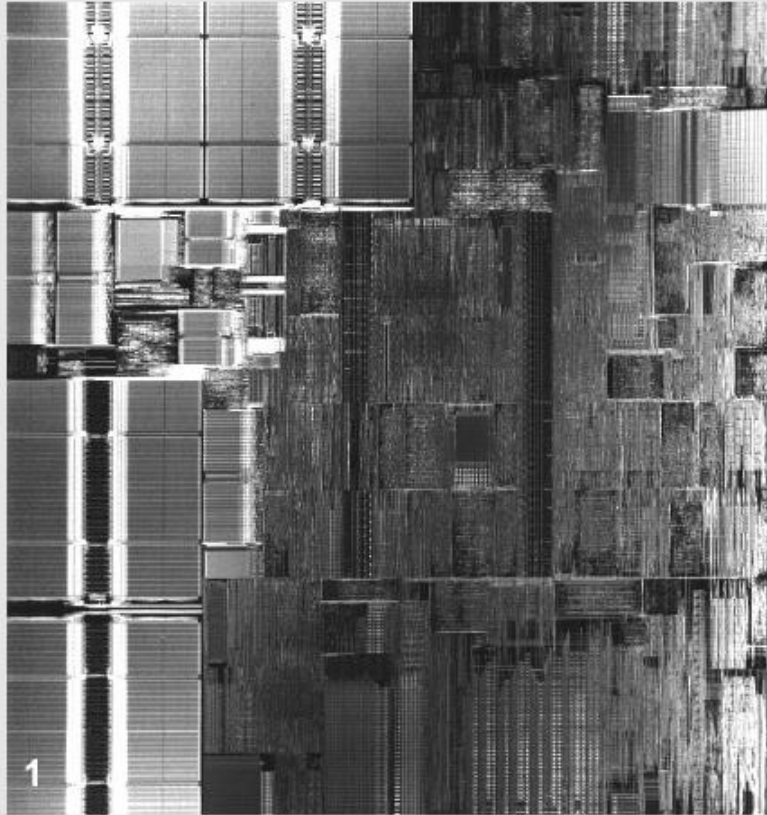- **Show different view all together**

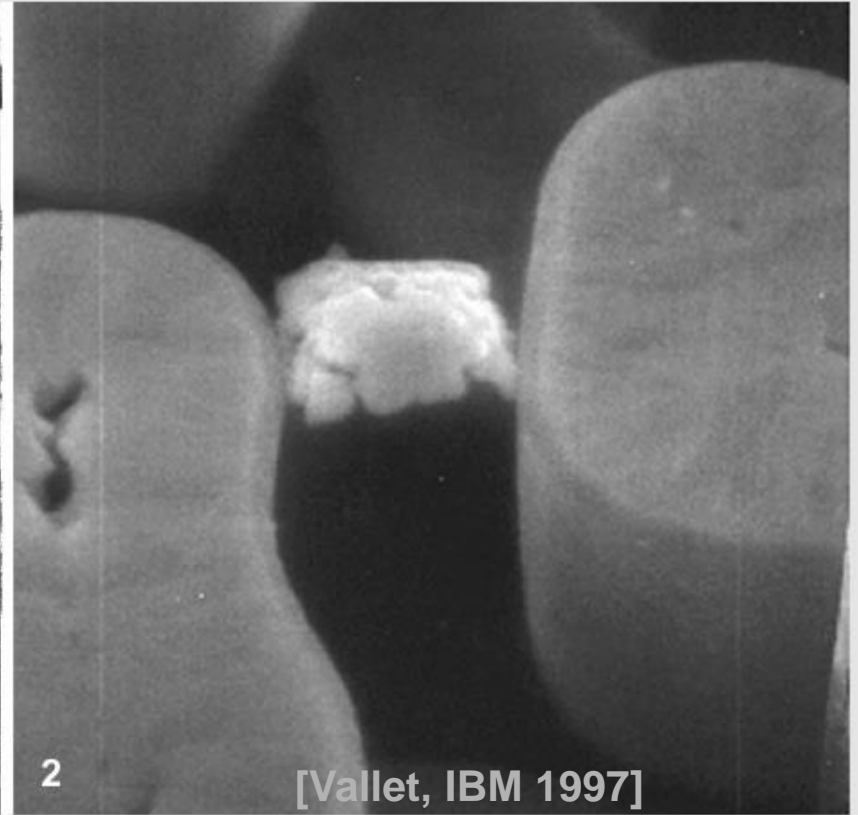Scope

Schematic

SEM

Layout

[image courtesy of SK Lu from FJU]

Challenges of Failure Analysis

- **# 1 challenge: Looking for a needle in haystack …**
  - **Good software diagnosis is very important**

5M Transistor Microprocessor, 196mm²   0.2x0.4µm², nickel particle causing short

[Vallet, IBM 1997]

- **FA equipment are expensive**

FA Equipment Costly

- **Cost of useful FA tools (USD)**
  - ♦ **Microscope: 50K**
  - ♦ **X-ray: 150K**
  - ♦ **CSAM: 150K**
  - ♦ **Decapsulator: 40K**
  - ♦ **Automatic curve tracer: 100K**
  - ♦ **SEM: 200K**
  - ♦ **LEM: 150K**
  - ♦ **Probe station: 100K(semi-auto)**
  - ♦ **FIB: 500K**
  - ♦ **E-Beam probe: 300K**

Diagnosis

- **Introduction**
- **Logic Diagnosis**
- **Scan Chain Diagnosis**
- **Failure Analysis**
- **<u>Conclusions</u>**

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Conclusion

- **Diagnosis important for yield improvement and quick time to market**
- **Categories**
  - **Logic Diagnosis**
    - **Model-based diagnosis: SSF, delay fault**
    - **Modeless diagnosis: inject and cure, SLAT**
  - **Scan chain diagnosis**

- **Diagnosis was usually embedded in ATPG**
  - **Mentor Graphics: Fastscan**
  - **Synopsys: Tetramax**
  - **Cadence: Encounter Test**
- **Now, diagnosis also available as independent tool**
  - **Mentor Graphics: Yield assist**

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